

Application No. 10/524,525  
Amendment Dated 5/3/10  
Reply to Office Action of 11/3/09

This listing of claims will replace all prior versions, and listings, of claims in the application.

**In the Claims:**

1-23. Canceled.

24. (CURRENTLY AMENDED) A method for the selective removal of material from the surface of a silicon-containing substrate supported in a container for forming a deepening, comprising the steps of:

applying a mask onto the substrate surface in accordance with a desired selective removal of material from the surface of the substrate, aluminium aluminum being used for forming the mask,

dry-etching the substrate to selectively remove material from the surface of the substrate, and

inductively coupling power into the etching medium during dry etching, the inductively coupled power provided by an inductive coupling coil in the form of a cylinder and having a lower edge,

wherein a cavity of a depth of at least 150 µm is generated at an etch rate of at least 2 µm/min,

in turn with etching steps passivation steps are included, and the substrate surface is kept at a distance from the lower edge of the inductive coupling coil of at least two times, preferably at least three times, the mean

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free path length of the plasma atoms, or at a distance of at least 8 cm from the lower edge of the inductive coupling coil.

25. (PREVIOUSLY PRESENTED) The method according to claim 24, characterized in that the substrate is kept at a distance of at least 10 cm from the inductive coupling.
26. (PREVIOUSLY PRESENTED) The method according to claim 24, characterized in that during etching the pressure is below 15 Pa, preferably below 10 Pa, and/or above 1 Pa, preferably above 2 Pa.
27. (PREVIOUSLY PRESENTED) The method according to claim 24, characterized in that material is removed up to the other side of the substrate.
28. (PREVIOUSLY PRESENTED) The method according to claim 24, characterized in that a mask having a thickness of below 1.5  $\mu\text{m}$ , preferably below 0.6  $\mu\text{m}$ , is formed.
29. (PREVIOUSLY PRESENTED) The method according to claim 24, characterized in that the substrate is masked up to the edge.

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30. (PREVIOUSLY PRESENTED) The method according to claim 24,  
characterized in that when the mask is applied aluminum is vapor-deposited or  
sputtered.
31. (PREVIOUSLY PRESENTED) The method according to claim 24,  
characterized in that when the mask is applied a metallic layer is etched in accordance  
with the desired selective removal.
32. (PREVIOUSLY PRESENTED) The method according to claim 24,  
characterized in that the metal used contains at least 90% by weight Al.
33. (PREVIOUSLY PRESENTED) The method according to claim 24,  
characterized in that the etch position (T) is determined repeatedly in the depthwise  
direction, etching being concluded or a second etching process, which is qualitatively  
different or proceeds with operating parameters differing from those of the preceding  
etching process, being employed when a certain position has been reached.
34. (PREVIOUSLY PRESENTED) The method according to claim 33,  
characterized in that the depth is determined by means of laser light whose properties  
are analyzed after being reflected by the bottom, in particular with respect to the first  
derivative of a detected signal.

35. (PREVIOUSLY PRESENTED) The method according to claim 33,  
characterized in that in the second etching process etching is carried out in a dry  
condition with inductively power-coupled plasma, the gas pressure being higher and/or  
the applied bias being lower.

36. (PREVIOUSLY PRESENTED) The method according to claim 34,  
characterized in that in the second etching process etching is carried out in a dry  
condition with inductively power-coupled plasma, the gas pressure being higher and/or  
the applied bias being lower.

37. (PREVIOUSLY PRESENTED) The method according to claim 33,  
characterized in that after the second etching process a third etching process is applied  
which is qualitatively different from the preceding etching process or proceeds with  
operating parameters differing from those of the preceding etching process.

38. (PREVIOUSLY PRESENTED) The method according to claim 34,  
characterized in that after the second etching process a third etching process is applied  
which is qualitatively different from the preceding etching process or proceeds with  
operating parameters differing from those of the preceding etching process.

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39. (PREVIOUSLY PRESENTED) The method according to claim 35,  
characterized in that after the second etching process a third etching process is applied  
which is qualitatively different from the preceding etching process or proceeds with  
operating parameters differing from those of the preceding etching process.

40. (PREVIOUSLY PRESENTED) The method according to claim 37,  
characterized in that in the third etching process etching is carried out in a dry and  
isotropic condition and preferably with inductively power-coupled plasma, wherein the  
applied bias may be 0.

41. (PREVIOUSLY PRESENTED) The method according to claim 24,  
characterized in that before the mask is removed an incineration step for polymer  
residues on the mask is preferably provided by wet etching.

42. (PREVIOUSLY PRESENTED) The method according to claim 41,  
characterized in that the incineration is effected by means of oxygen plasma.

43. (PREVIOUSLY PRESENTED) The method according to claim 41,  
characterized in that the incineration is followed by a treatment with  
tetramethylammonium hydroxide.

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44. (PREVIOUSLY PRESENTED) The method according to claim 42,  
characterized in that the incineration is followed by a treatment with  
tetramethylammonium hydroxide.
45. (PREVIOUSLY PRESENTED) The method according to claim 24,  
characterized by one or more of the following features:  
the material is removed from more than 8%, preferably more than 20%, of  
the substrate surface,  
the substrate is a disk-like wafer having a diameter of at least 10 cm,  
preferably at least 15 cm.

46. CANCELED.

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47. (CURRENTLY AMENDED) A method for masking a wafers wafer to be etched with a mask material and etching the masked wafer, comprising:

applying a mask material to a wafer to be etched in accordance with a desired selective removal of material from a surface of the wafer, wherein the material comprises:

an aluminum amount of more than 90% by weight, preferably more than 95% by weight, and

a copper amount between 0.5 and 2% by weight, preferably ~~below 1%~~ by weight, and/or a silicon amount between 0.5 and 2% by weight and/or a titanium amount between 0.2% by weight and 3% by weight, preferably ~~below 1.5%~~ by weight, are admixed to form the mask material[[.]]; and

etching the masked wafer in accordance with the desired selective removal of material from the surface of the wafer.

48. CANCELED.

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49. (CURRENTLY AMENDED) A method for the selective removal of material from the surface of a silicon-containing substrate supported in a container for forming a deepening, comprising the steps of:

applying a mask onto the substrate surface in accordance with a desired selective removal of material from the surface of the substrate, aluminium aluminum being used for forming the mask,

dry-etching the substrate to selectively remove material from the surface of the substrate, and

inductively coupling power into the etching medium during dry etching, the inductively coupled power provided by an inductive coupling coil in the form of a cylinder and having a lower edge,

wherein a cavity which fully penetrates through the substrate is generated at an etch rate of 2  $\mu\text{m}/\text{min}$ ,

in turn with etching steps passivation steps are included, and the substrate surface is kept at a distance from the lower edge of the inductive coupling coil of at least two times, preferably at least three times, the mean free path length of the plasma atoms, or at a distance of at least 8 cm from the lower edge of the inductive coupling coil, an electric field is applied between the substrate and the inductive coupling coil.

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50. (PREVIOUSLY PRESENTED) A method for the selective removal of material from the surface of a silicon-containing substrate supported in a container for forming a deepening, comprising the steps of:

applying a mask onto the substrate surface in accordance with a desired selective removal of material from the surface of the substrate, aluminium aluminum or an aluminum alloy having at least 90% by weight Al or of a composite material having at least 90% by weight Al being used for forming the mask,

dry-etching the substrate to selectively remove material from the surface of the substrate, and

inductively coupling power into the etching medium during dry etching using an inductively power-coupled plasma, the inductively coupled power provided by an inductive coupling coil in the form of a cylinder and having a lower edge,

wherein a cavity of a depth of at least 300  $\mu\text{m}$  is generated at an etch rate of at least 2  $\mu\text{m}/\text{min}$ ,

in turn with etching steps passivation steps are included, and the substrate surface is kept at a distance from the lower edge of the inductive coupling coil of at least two times, preferably at least three times, the mean free path length of the plasma atoms, or at a distance of at least 8 cm from the lower edge of the inductive coupling coil.